Fig.1

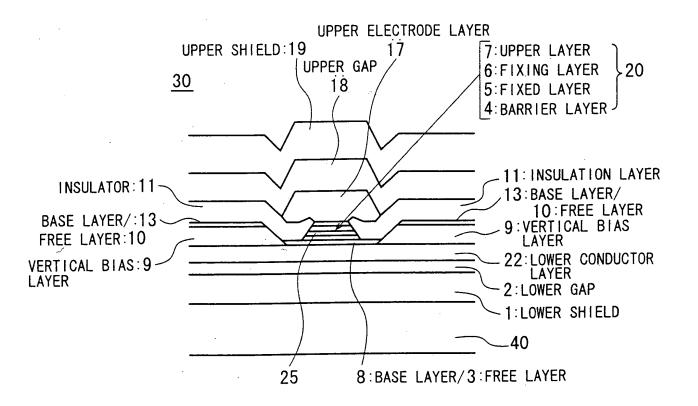


Fig.2

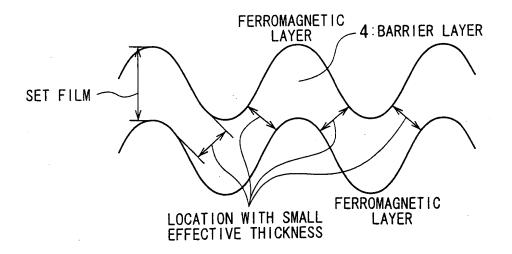


Fig.3

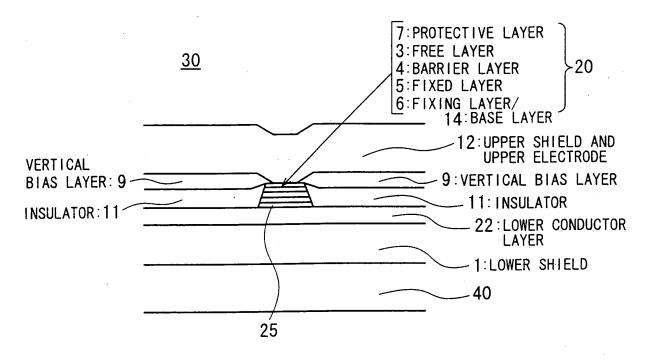
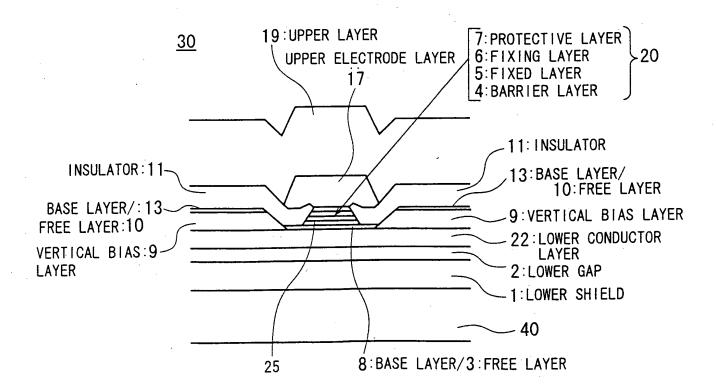


Fig.4





Invention Title: Magnetoresistive Effect Sensor
Inventor: Hayashi, Kazuhiko
Det No./Application No: NEC2370-US:09/853,022
Replacement Sheet

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Fig.5

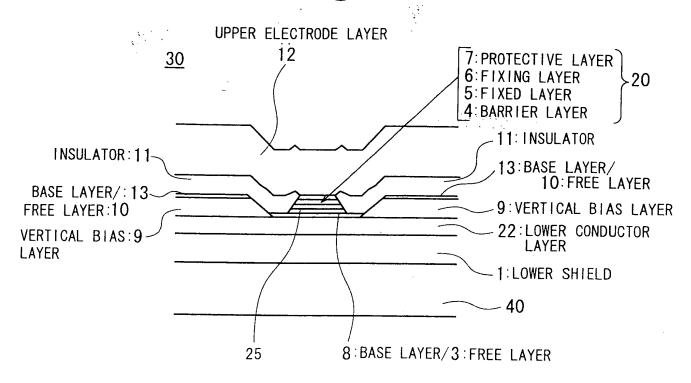


Fig.6

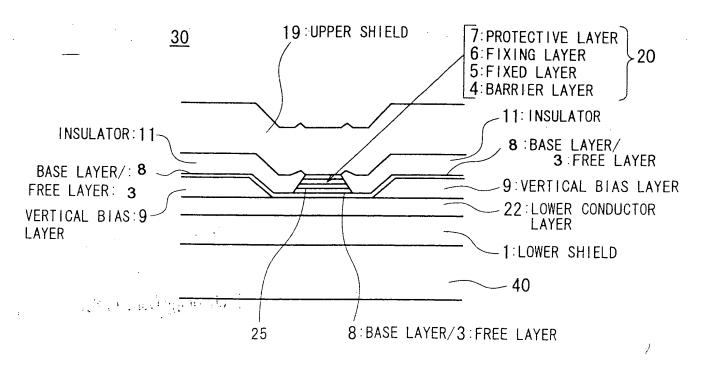


Fig.7

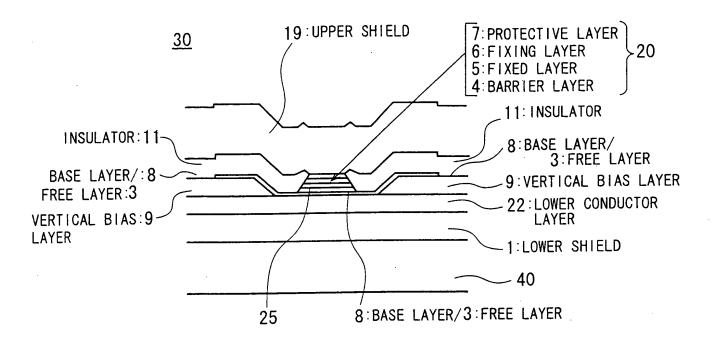


Fig.8

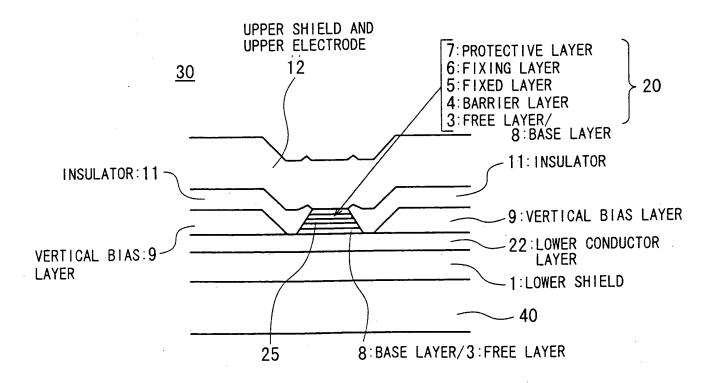
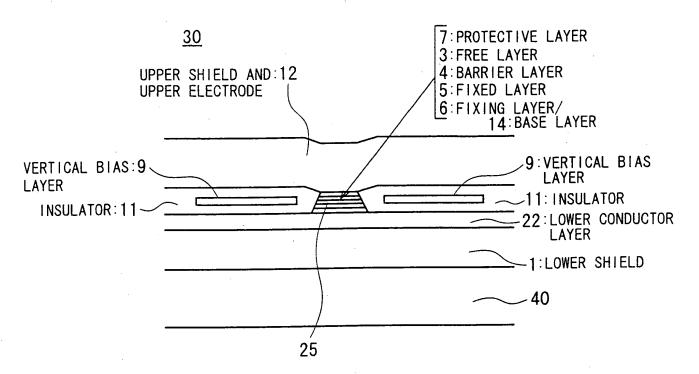
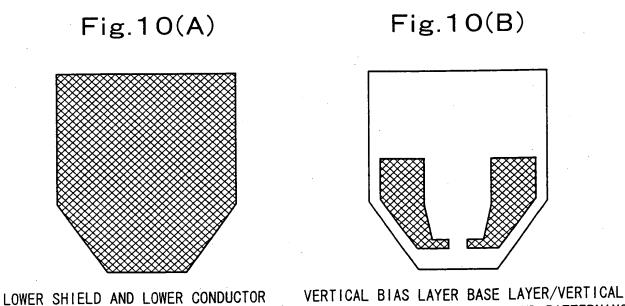


Fig.9





LAYER FORMED AS FILMS AND PATTERNED

 $(PR FORMATION \rightarrow PR REMOVAL)$

BIAS LAYER FILM FORMATION AND PATTERNING

 $(PR FORMATION \rightarrow PR REMOVAL)$

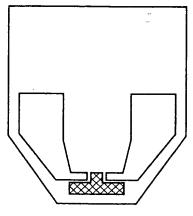


Invention Title: Magnetoresistive Effect Sensor Inventor: Hayashi, Kazuhiko et No./Application No: NEC2370-US:09/853,6

Replacement Sheet

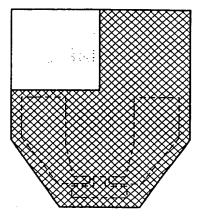
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Fig. 11(A)



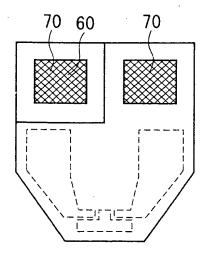
PR FORMATION \rightarrow MILLING \rightarrow INSULATION FILM FORMATION → LIFT-OFF

Fig.11(B)



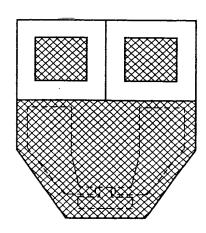
MAGNETORESISTIVE EFFECT FILM ightarrow UPPER SHIELD FORMATION ightarrow PR FORMATION → PATTERNING → PR REMOVAL

Fig.12(A)



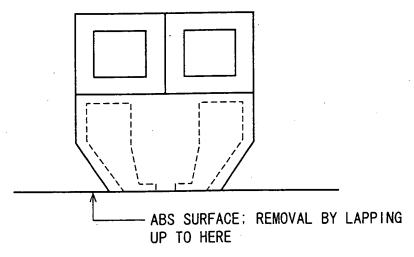
LOWER ELECTRODE HOLE FORMATION. ELECTRODE TERMINAL FORMATION

Fig. 12(B)



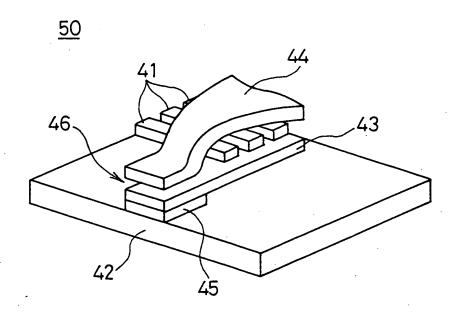
RECORDING HEAD FORMATION

Fig.13



FORMATION OF ABS SURFACE BY LAPPING

Fig.14



'nZ.

Fig.15

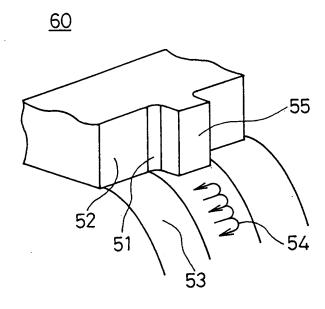


Fig.16

